

## Patent Abstracts of Japan

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TITLE

: PRODUCTION OF SILANE COMPOUND

PSTRACT :

PROBLEM TO BE SOLVED: To provide a method for producing a silane compound, enabling the production of the silane compound having a specific structure at a low cost in a high purity and further enabling the control of the production of a disiloxane compound which is a useful by-product, by reacting a specific oxysilane with a specific disiloxane and a carboxylic acid in the presence of a strong acid.

SOLUTION: This method for producing a silane compound of the formula: R1Si(OSiR3R4R5)3 comprises reacting (A) a compound of the formula: R1Si(OR2)3 (R1 is a ≤15C alkyl, an aryl or the like; R2 is a ≤15C alkyl, a ≤10C arylalkyl or the like) (for example, 3-methacryloyloxypropyltrimethoxysilane) with (B) a compound of the formula: (R3R4R5Si)2O (R3, R4, R5 are each H, a ≤15C alkyl or the like) (for example, hexamethyldisiloxane) and (C) a carboxylic acid (preferably acetic acid) in the presence of a strong acid (preferably concentrated sulfuric acid). It is preferable for the control of by-products that the component A is dropwisely added and reacted with a mixture of the components B, C and the strong acid at -10 to 0°C for a dropping time of ≤30 min and then aged.

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